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Jul 20, 1995

DERWENT-ACC-NO: 1995-263880

DERWENT-WEEK: 199610

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TITLE: Depositing oxide-contg metal or metalloid layer - using cold nitrogen plasma to decompose metal or metalloid alkyl.

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PRIORITY-DATA: 1994FR-0000387 (January 14, 1994)

PATENT-FAMILY:

PUB-NO PUB-DATE LANGUAGE PAGES MAIN-IPC WO 9519456 A1 July 20, 1995 F 019 C23C016/02 NZ 270340 A January 26, 1996 000 C23C016/18 July 21, 1995 016 C23C016/18 AU 9515390 A August 1, 1995 000 C23C016/02

INT-CL (IPC):  $\underline{B05}$   $\underline{D}$   $\underline{3/04}$ ;  $\underline{C08}$   $\underline{J}$   $\underline{7/04}$ ;  $\underline{C08}$   $\underline{J}$   $\underline{7/06}$ ;  $\underline{C23}$   $\underline{C}$   $\underline{16/02}$ ;  $\underline{C23}$   $\underline{C}$   $\underline{16/18}$ ;  $\underline{C23}$   $\underline{C}$   $\underline{16/50}$ ;  $\underline{C23}$   $\underline{C}$   $\underline{16/52}$ ;  $\underline{H05}$   $\underline{H}$   $\underline{1/00}$ 

ABSTRACTED-PUB-NO: WO 9519456A

BASIC-ABSTRACT:

In the deposition of a layer of gp IIb, IIIa, IVa or Va metal or metalloid and its oxide, in which the substrate (14) is pretreated with a deferred cold nitrogen plasma consisting of free nitrogen atoms in a chamber (13), the novelty is that, after substrate pretreatment, a volatile metal or metalloid alkyl (10) is introduced into the chamber (13) to form a layer, comprising a mixt of the metal or metalloid and its oxide, on the substrate (14).

ADVANTAGE - Highly adherent deposits, esp of zinc and zinc oxide, can be produced at ambient temp on any substrate, e.g. metals, alloys, ceramics, polymers, composite materials and glasses, to obtain a conductive, decorative or corrosion or erosion protective surface.